## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of

Ryota Nanjo et al

Serial No.: 10/084,367

Group Art Unit: Not Yet Assigned

Filed: February 28, 2002 Examiner: Not Yet Assigned

For: SEMICONDUCTOR DEVICE AND ITS MANUFACTURE

## INFORMATION DISCLOSURE STATEMENT PURSUANT TO 37 CFR 1.97(b)

Commissioner for Patents Washington, D.C. 20231

April 25, 2002

Sir:

The attention of the Patent and Trademark Office is hereby directed to the documents listed on the attached Form PTO-1449. One copy of each of these documents is attached.

No fee or certification is required in connection with this Information Disclosure Statement, since it is being submitted prior to the issuance of a first official action on the merits or expiration of the three month period following filing of the above-captioned application.

The above information is presented so that the Patent and Trademark Office can, in the first instance, determine any materiality thereof to the claimed invention. See 37 CFR 1.164(a) and 1.106(b) concerning the PTO duty to consider and use any such information. It is respectfully requested that the information be expressly considered during the prosecution of this application, and that the documents cited in the attached Form PTO-1449 be made of record therein and appear of the first page of any patent to issue therefrom.

Serial No.: 10/084,367

The Commissioner is authorized to charge our Deposit Account No. 01-2340 for any fee which is deemed by the Patent and Trademark Office to be required to effect consideration of this statement.

Respectfully submitted,

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DWH/nk

Enclosures: PTO-1449, 11 references

INFORMATION DISCLOSURE CURATION #3			Atty. Docket No. 020200			Serial No. 10/084,367			
			Applicant(s): Ryota Nanjo et al						
190-1449 °			Filing I	Date: February	28, 2002	Group Art Unit: Not Yet Assigned			
U.S. PATENT DOCUMENTS									
Examiner Date Class Subclass Filing Date Initial (If appropriate the control of t									
	AA	5,956,603 Talwar et al			9/21/99	438	520		
FOREIGN PATENT DOCUMENTS									
Document No.					Date	Country	·	Translation (Yes or No)	
	AF	2001-007220			1/12/01	JP		Yes, abstract	
	AG	2000-269491			9/29/00	JP		Yes, abstract	
	AH	2000-196037			7/14/00	JP		Yes, abstract	
	AI	07-231044			8/29/95	JP		Yes, abstract	
	AJ	06-053	3157		2/25/94	JP		Yes, abstract	
	AK	05-06	7776		3/19/93	JP		Yes, abstract	
OTHER DOCUMENTS									
	AL	Phosp	"Activation and Deactivation of Laser Thermal Annealed Boron, Arsenic, Phosphorus and Antimony Ultra-Shallow Abrupt Junctions", Murto et al; TH-13; Ion Implantation Technology 2000 "Self-Aligned Nickel-Mono-Silicide Technology for High-Speed Deep Submicrometer Logic CMOS USI", Morimoto et al; Vol 42, No. 5, May 1995 IEEE,						
	AM	"Self-							
	AN	"70nn	pp 915-923.  "70nm MOSFET with Ultra-shallow, Abrupt, and Super-doped S/D Extension Implemented by Laser Thermal Process (LTP); Bin Yu et al; 1999 EEE						
	AO	"Fron	"Front End Processes"; International Technology Roadmap for Semiconductors 1999; pp 105-141						

Date Considered

Examiner